

2013 International Symposium on Extreme Ultraviolet Lithography

Toyama, Japan ● 6 - 10 October, 2013



Opening Remarks

Ichiro Mori, Soichi Inoue
EIDEC

TOYAMA, JAPAN
Oct. 7, 2013



Welcome to the 2013 EUVL Symposium!

2013 International Symposium on
Extreme Ultraviolet Lithography
Toyama, Japan • 6 - 10 October, 2013

Organized by:



In cooperation with:



Symposium Chair:

Symposium Co-Chairs:

Ichiro Mori (EIDEDEC)

Toshiro Itani (EIDEDEC)

Kurt Ronse (imec)

Stefan Wurm (SEMATECH)

Welcome to the 2013 EUVL Symposium!

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Program Chair:

Program Co-Chairs:

Soichi Inoue (EIDEC)

Winfried Kaiser (Carl Zeiss SMT)

Patrick Naulleau (LBNL)

Seong-Sue Kim (Samsung)

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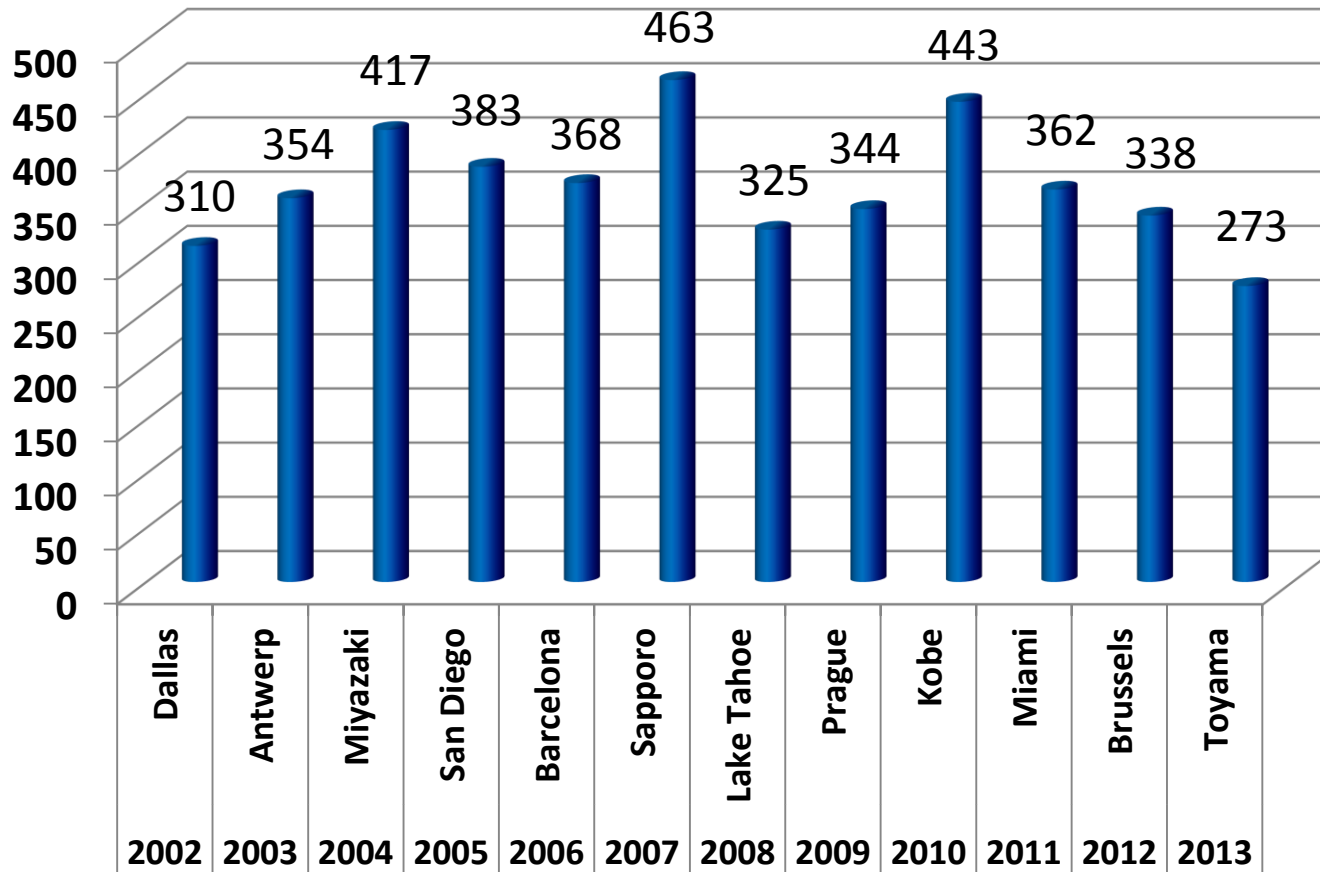
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2013 EUVL Symposium

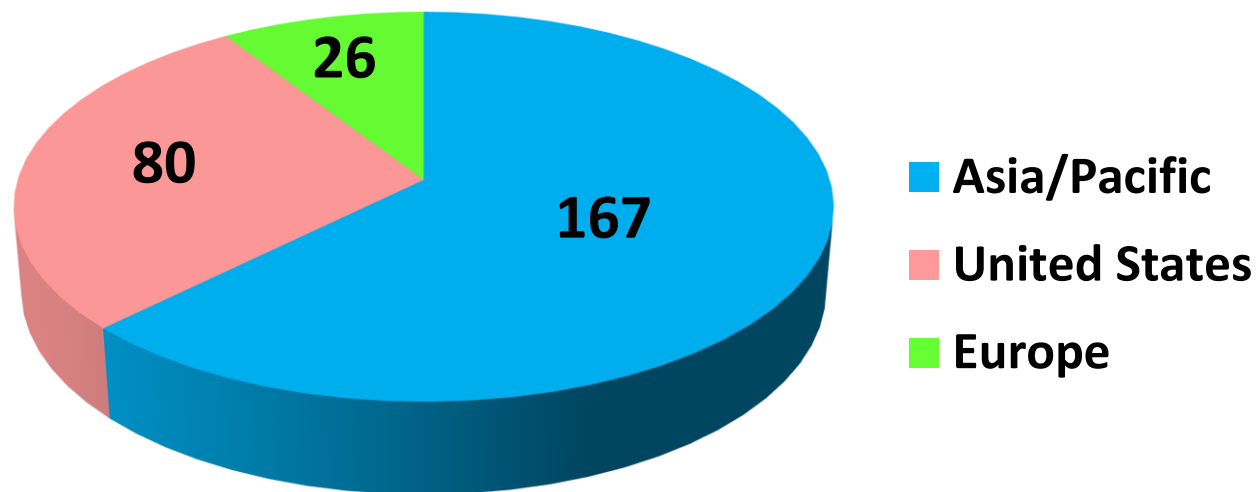
Attendance 1st to 12th Symposium (October 7th, 2013)

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Attendance by Geographic Region

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Challenge to Realization

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Breaking the Barrier of Technology and Economy for HVM: Extra Efforts in Realizing EUV Lithography

The industry has been moving forward to pilot manufacturing of the 20-16 nm half-pitch generation using EUVL, but significant challenges still remain.

Innovative Approaches for the Next Generation EUV Lithography: High NA Combined with Technologies to Extend EUV Lithography

To meet the challenges of 11 nm half-pitch to sub-10 nm feature size imaging with EUVL, the industry needs to explore new innovative, and aggressive approaches.

Keynote Presentation

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Dr. Anthony Yen

Director of Nanopatterning Technology Infrastructure Division
TSMC

**"Semiconductor Manufacturing Using EUV Lithography:
Progress and Remaining Challenges"**

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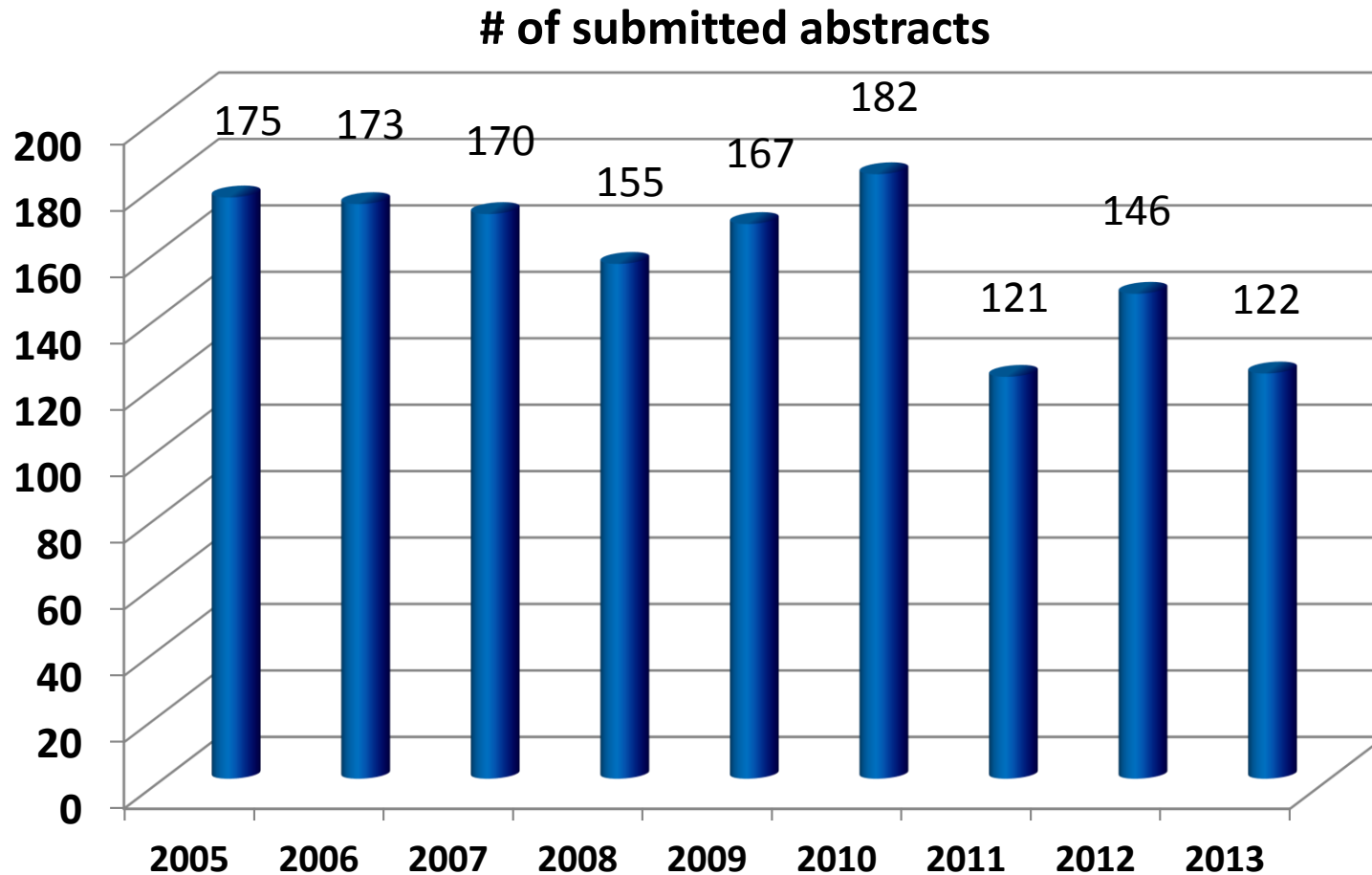
Program Overview

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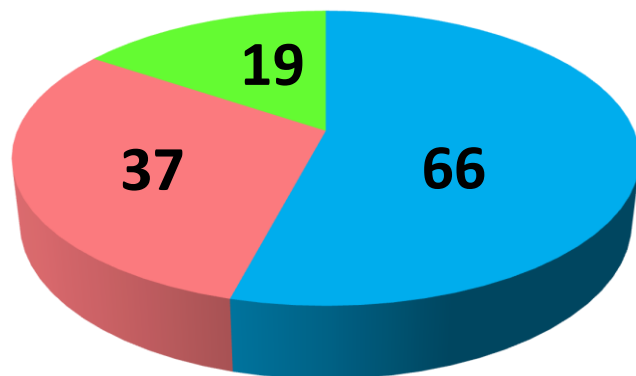
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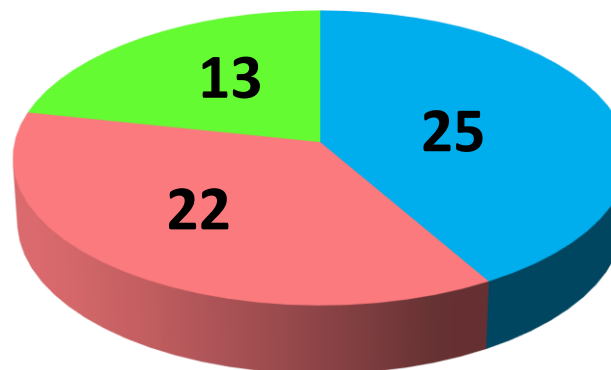
Contributions by Region

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Submitted Abstracts: 122



Oral Program: 60

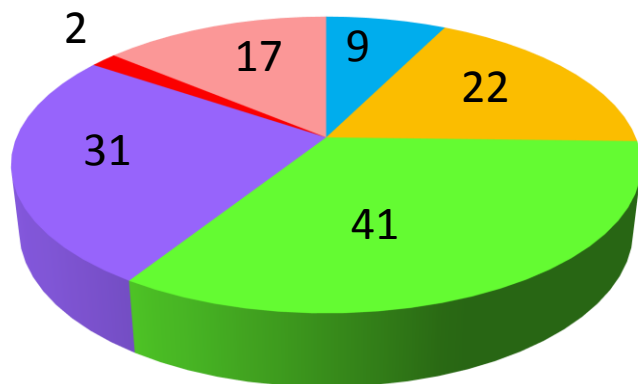


■ Asia/Pacific
■ US
■ Europe

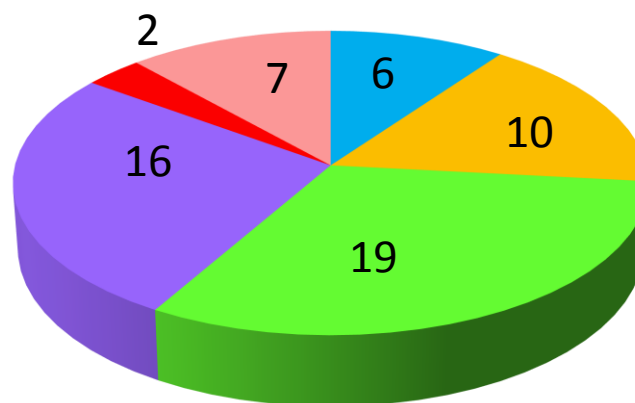
Contributions by Topic

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Submitted Abstracts: 122



Oral Program: 60



- Exposure Tools & Patterning
- Source-Collector & Optics
- Mask Fabrication, Metrology & Inspection
- Resist & process
- Integration
- EUV Extension

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Program at a Glance

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Oct. 7 Monday	Oct.8 Tuesday	Oct.9 Wednesday	Oct.10 Thursday
Keynote Presentation	Source	Resist Fundamentals	Collector & Optics
Exposure Tools & Patterning	Mask Inspection Tools	Resist Processing	Blank Process & Characterization
Lunch	Lunch	Lunch	Lunch
Mask Fabrication	Networking	EUV Extension	Resist Outgassing/ OoB
Resist & Materials		Mask Metrology & Imaging	
Poster Session 6:00pm~8:00pm		Conference Dinner 6:10pm~8:30pm	

For a detailed program, see agenda in your booklets

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Poster Session

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- ✓ **Monday, October 7 • 6:00 pm – 8:00 pm**
- ✓ **All posters must be ready by 5:00 pm Monday, October 7.**
- ✓ **Poster presenters are expected to stay at their poster during the scheduled poster session.**
- ✓ **The posters can remain up and available for the duration of the conference .**
- ✓ **We ask you not to take your poster down before the coffee break on Thursday 10:50 am.**

Conference Dinner

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- ✓ **Wednesday evening (Oct. 9th)**
- ✓ **Starts at 6:10 pm**
- ✓ **@ ANA Crowne Plaza Toyama, 3rd Floor
Banquet Hall “Ohtori”**

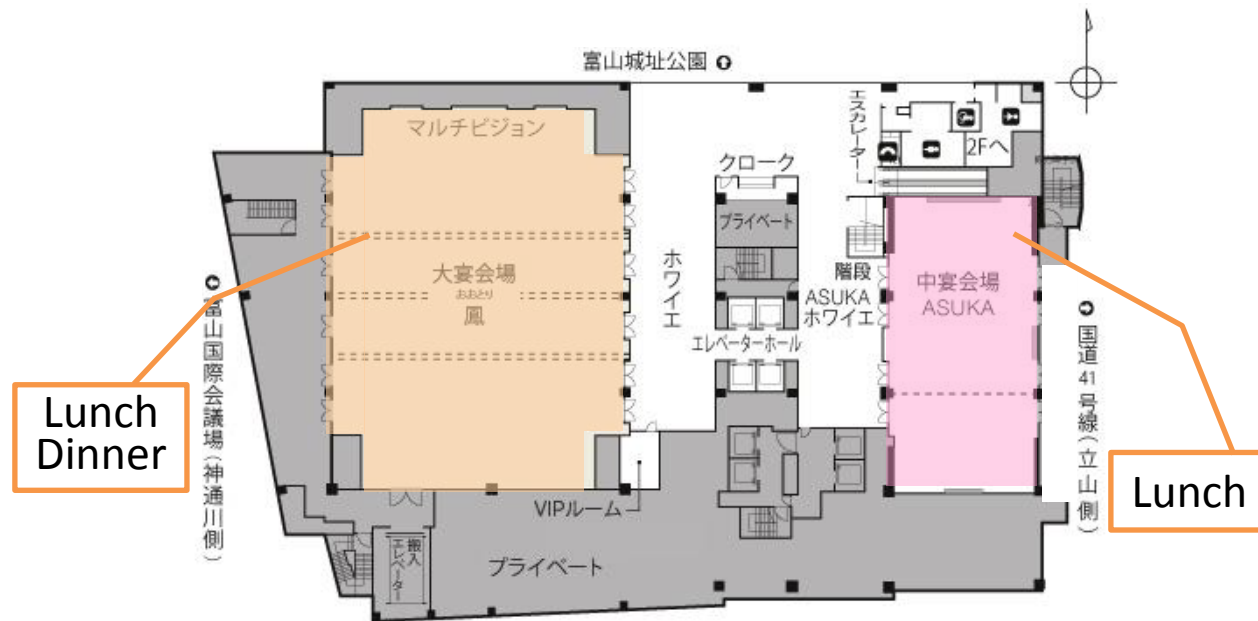
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Banquet Hall

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ANA Crowne Plaza Toyama

3rd Floor



Housekeeping

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✓ **For audience:**

- *Please use the audience microphones for your questions*
- *Put your cell phones in silent mode*
- *Taking pictures and recording are strictly prohibited*

✓ **For presenters:**

- *Turn it and check your presentations*
- *Stick to your allotted presentation time*

✓ **Presentations and posters will be distributed through the SEMATECH website after the symposium**

- *Notification will be sent by e-mail to all Symposium attendees*

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Oversight

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- ✓ ***Wednesday, October 9***
- ✓ ***Session 7 : Resist Processing***
- ✓ ***Session Chair: Taku Hirayama (TOK), Jan van Schoot (ASML)***



- ✓ ***Session Chair: Taku Hirayama (TOK), **Rudy Peeters (ASML)*****

2013 EUVL Symposium Support Team at the Symposium

Hotta

Iida

Marcy

Fukunaga

Uwatoko

Sakurai

Sumimoto

Sengoku



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**Please Enjoy
the Symposium and
Toyama!!**